

Title (en)
OPTICAL ELEMENT AND METHOD

Title (de)
OPTISCHES ELEMENT UND VERFAHREN

Title (fr)
ÉLÉMENT OPTIQUE ET PROCÉDÉ

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Application
EP 07818354 A 20070921

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Abstract (en)
[origin: WO2008034636A2] The invention relates to an optical element (1) for at least partial, localised correction of a wavefront error of an optical system irradiated by an optical beam, comprising a region optically active with regard to the optical beam and electrical conductor tracks (3) in said optically active region, said electrical conductor tracks having, at least partly, a diameter of at most 50 micrometres lateral to the direction of incidence of the optical beam.

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See references of WO 2008034636A2

Citation (examination)
EP 1921505 A1 20080514 - ASML NETHERLANDS BV [NL], et al

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KR 101493535 B1 20150213; KR 20090058575 A 20090609; US 2009257032 A1 20091015; US 2011080569 A1 20110407;
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